



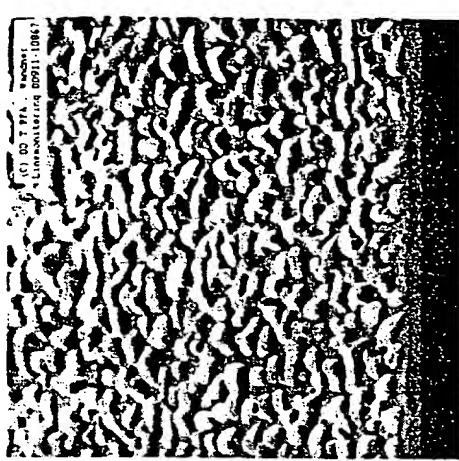
Silicon Seeding on Flat Oxide Wafers

AVP 8000

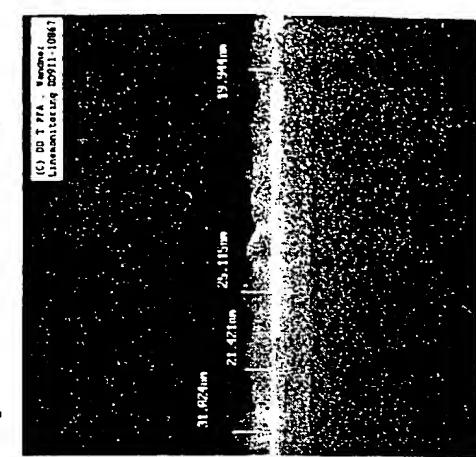
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Variation of the Silane Dilution: Influence on Grain Density and Height

N2 dilution 1:10 / 15 min



N2 dilution 1:5 / 15 min

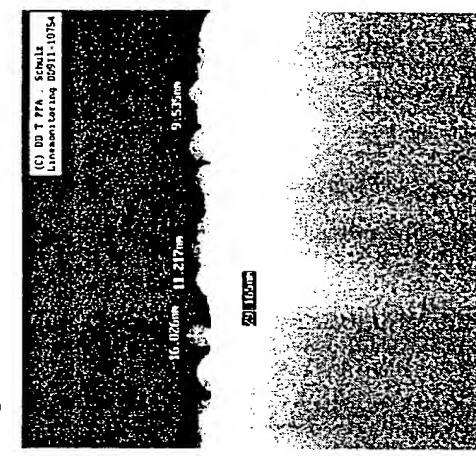


ગુજરાત સરકાર

15 min

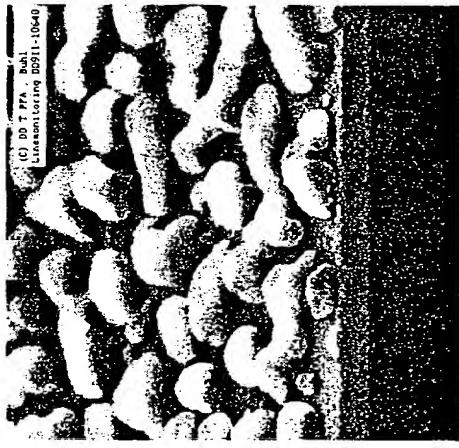


18751-81 ZR889550.18 center x188k/10kU/68° 0.1μm

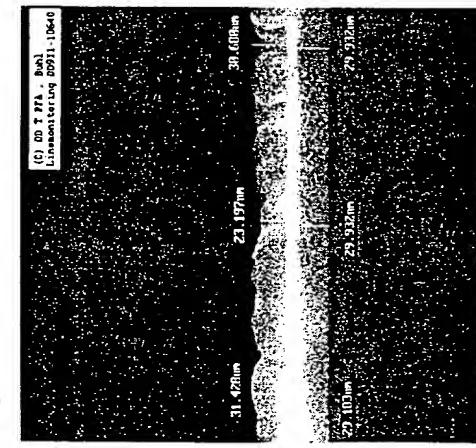


1977-1982 248895529.18 HSC Centre x48895529U 8.1m

no N₂ dilution / 6 min



198-10-86 23895535.98 Center 3666660/1986 0.1m



18610-05 ZR089550.00 center 3800000x10XU 0.144

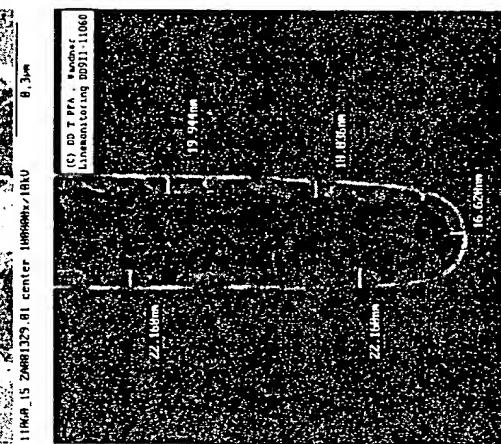
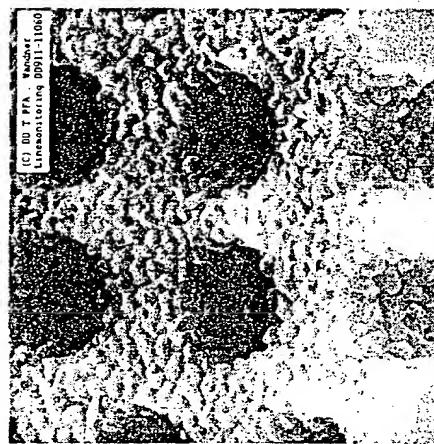
Silicon Seeding on Deep Trench Wafers

O P E N JC95
FEB 12 2003
PATENT & TRADEMARK OFFICE

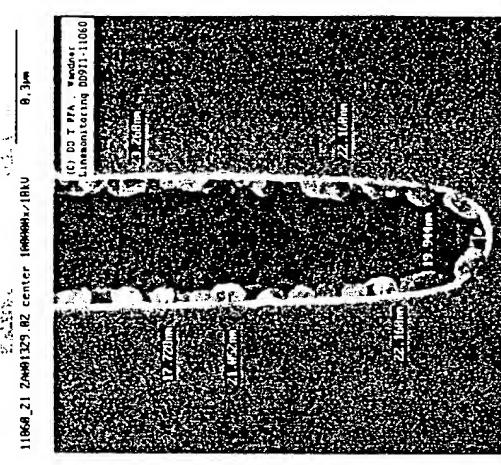
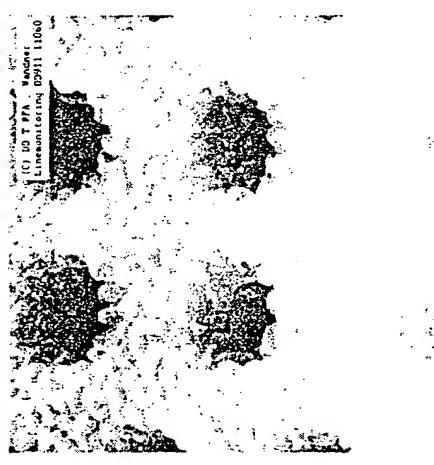
AVP 8000

Variation of the Predean: Influence on Grain Density and Height

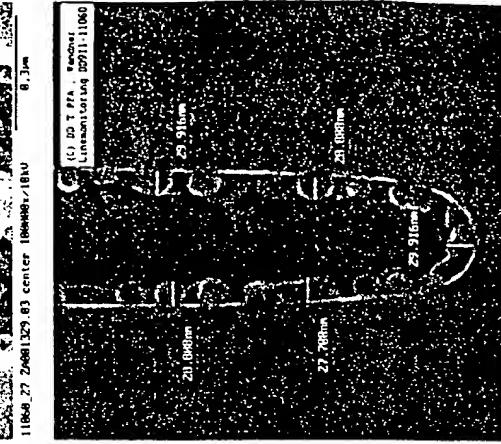
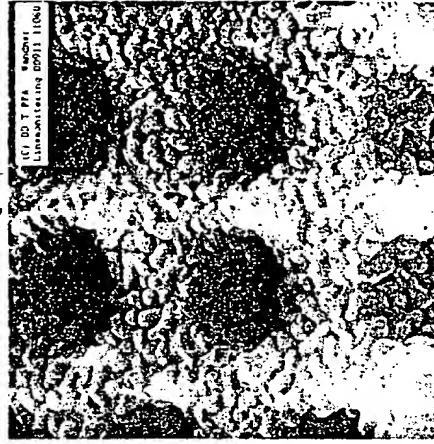
CLEAN WET PIRANHA only



CLEAN WET DFI/HUANG MEGASONIC



HF LAST → 8.10µm / 8.10µm



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AMORENCE
M. J. Foster